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MOLECULAR IMPRINTS AND MIT REACH TECHNOLOGY LICENSING AGREEMENT

AUSTIN, TX, November 30, 2004 – Molecular Imprints, Inc. (MII), the leading manufacturer of Step and Flash Imprint Lithography (S-FIL™) technology, has completed an exclusive licensing agreement with the Massachusetts Institute of Technology for the use of the university's moiré fringe alignment technology, in MII's nano imprint lithography tools.

MII anticipates using this technology as a primary vehicle for high resolution alignment in advanced lithography applications. MII's CTO, Dr. Sreenivasan, and his team have demonstrated 7nm, 3sigma alignment with this technique, on an MII tool.

Professor Hank Smith from the Massachusetts Institute of Technology led the effort to develop this technology and will be part of the ongoing development efforts.

"I believe this is a very strong collaborative agreement, coupled with strong research and development efforts, to advance the state of Step and Flash Imprint Lithography." states MII's CEO Norm Schumaker.

About Molecular Imprints Inc.

Molecular Imprints, Incorporated (MII) develops and manufactures nano-lithography systems for high resolution and for 3-dimensional pattern replication. The company has commercialized a unique Step and Flash Imprint Lithography technology (S-FIL), which is a simple step and repeat, room temperature, low pressure, nano-imprint process that has demonstrated sub-20 nanometer resolution. Molecular Imprints provides enabling lithography systems and technology for manufacturing applications in the areas of: nano-devices, micro structures, advanced packaging, bio-devices, optical components and semiconducting devices. For more information, visit: www.molecularimprints.com.

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